

Substitute for Form 1449A/PTO & 1449B/PTO		Complete if Known	
FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/764,407
(use as many sheets as necessary)		Filing Date	January 23, 2004
		First Named Inventor	Shenggao Liu et al.
		Examiner Name	
Sheet	3	of	3
		Attorney Docket Number	

FOREIGN PATENT DOCUMENTS

NON-PATENT LITERATURE DOCUMENTS

Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume/issue number(s), publisher, city and/or country where published.
GJ	LIAW, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantanate," <i>Macromol. Chem. Phys.</i> 200, No. 6, pp. 1326-1332 (1999)
GJ	NOZAKI, Koji et al., "High-Performance Resist Materials for Ar/F Excimer Laser and Electron Beam Lithography," <i>FUJITSU Sci. Tech. J.</i> , 38, 1, pp. 3-12 (June 2002)
GJ	PADMANABAN, Munirathna, et al., "Etch Properties of 193nm Resists: Issues and Approaches," <i>Journal of Photopolymer Science and Technology</i> , Vol. 15, No. 3 (2002), pp. 521-528
GJ	PADMANABAN, Munirathna, et al., "Layer-Specific Resists for 193nm Lithography," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 607-616
GJ	PANIEZ, P. J., et al., "Thermal Phenomena in Acrylic 193 nm Resists," <i>SPIE Conferences on Advances in Resist Technology and Processing XVI</i> , Santa Clara, CA, SPIE Vol. 3678 pp. 1352-1363 JUNE 1999 /CH/ 10/1/08
GJ	SHIDA, Naomi, "Advanced Materials for 193-nm Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 601-606
GJ	USHIROGOUCHI, Tohru, et al., "Advanced Materials for 193-nm Resists," In <i>Advances in Resist Technology and Processing XVII</i> , Francis M. Houlihan, Editor, Proceedings of SPIE Vol. 3999 (2000) pp. 1147-1156

Examiner
Signature

Date Considered

see Cross-File through citation

***EXAMINER:** Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.